

Seat No.: _____

Enrolment No. _____

GUJARAT TECHNOLOGICAL UNIVERSITY**M.E –IIst SEMESTER–EXAMINATION – JULY- 2012****Subject code: 1720311****Date: 14/07/2012****Subject Name: Microelectromechanical Systems****Time: 10:30 am – 13:00 pm****Total Marks: 70****Instructions:**

1. Attempt all questions.
2. Make suitable assumptions wherever necessary.
3. Figures to the right indicate full marks.

Q.1	(a)	Discuss various applications of Smart materials and Microsystems.	07
	(b)	Why we need microfabrication for the development of IC fabrication process?	07
Q.2	(a)	Discuss conductometric gas sensor in detail.	07
	(b)	Draw a sketch and explain comb- drive.	07
		OR	
	(b)	What is micromirror array? How it is useful in video projection?	07
Q.3	(a)	Compare major process steps in lithography and lift-off based patterning.	07
	(b)	What is the difference between Isotropic and Anisotropic etching?	07
		OR	
Q.3	(a)	Explain bulk micromachining in detail.	07
	(b)	A (100) silicon wafer is 500 μm thick. A mask consists of rectangular window of unknown size. The sides of the window are parallel to $\langle 100 \rangle$. After wafer etch a hole size of 50 μm x 80 μm is formed on the other side of the wafer. Find the size of the mask window. The undercut rate is negligible.	07
Q.4	(a)	Explain the different process steps involved in the surface micro machining technology for realizing a polysilicon cantilever beam.	07
	(b)	Discuss methods to avoid stiction in RF-MEMS switches.	07
		OR	
Q.4	(a)	Write a note on Bimorph effect.	07
	(b)	Discuss Castigliano's theorems.	07
Q.5		Discuss Metal packages, Ceramic packaging, LTCC packages and Plastic packages.	14
		OR	
Q.5	(a)	Discuss Flip- Chip assembly technology.	07
	(b)	Discuss Ball- Grid array.	07

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